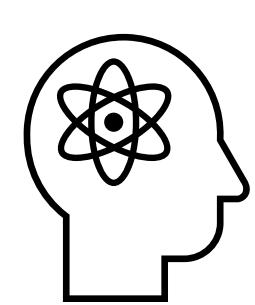


A thin-layer hafnium oxide as auxiliary layer obtained by atomic layer deposition onto macroporous silicon for SERS



K. Girel^{1,2}, K. Litvinova³, A. Burko^{1,2}, S. Dubkov², A. Savitsky², D. Novikov², A. Tarasov², H. Bandarenka^{1,2}

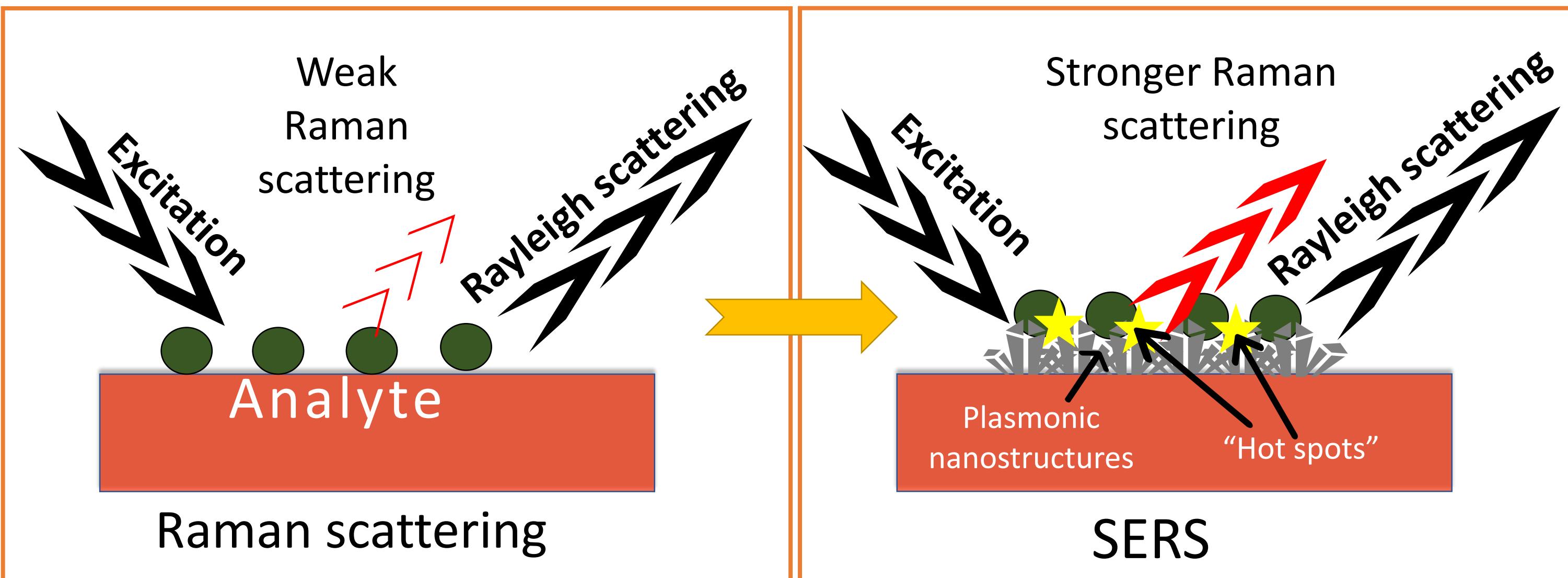
¹ Belarusian State University of Informatics and Radioelectronics, 6 P.Brovki st., Minsk, 220013, Belarus

² Institute of Advanced Materials and Technologies, National University of Electronic Technology, 1 Shokin Sq., Zelenograd, Moscow, 124498, Russia

³ National University of Science and Technology Leninskiy Prospekt 4, NUST MISIS, Moscow, 119049, Russia

What is SERS?

Surface-enhanced Raman scattering



Opportunities of SERS

Label-free detection of biomarkers

Study of chemical reactions

Explosives' and toxins' sensing

Early clinical diagnostics

Environmental/food/industrial surveillance

Problems of SERS-substrates

Chemical instability

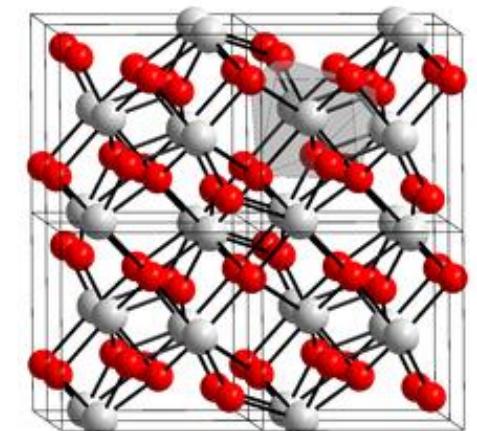
Disposable

Cytotoxicity

Photothermal effect

Solution – plasmonic nanostructures on biocompatible template modified with auxiliary oxide layer → Porous Si (PS) + HfO_x

Hafnium oxide

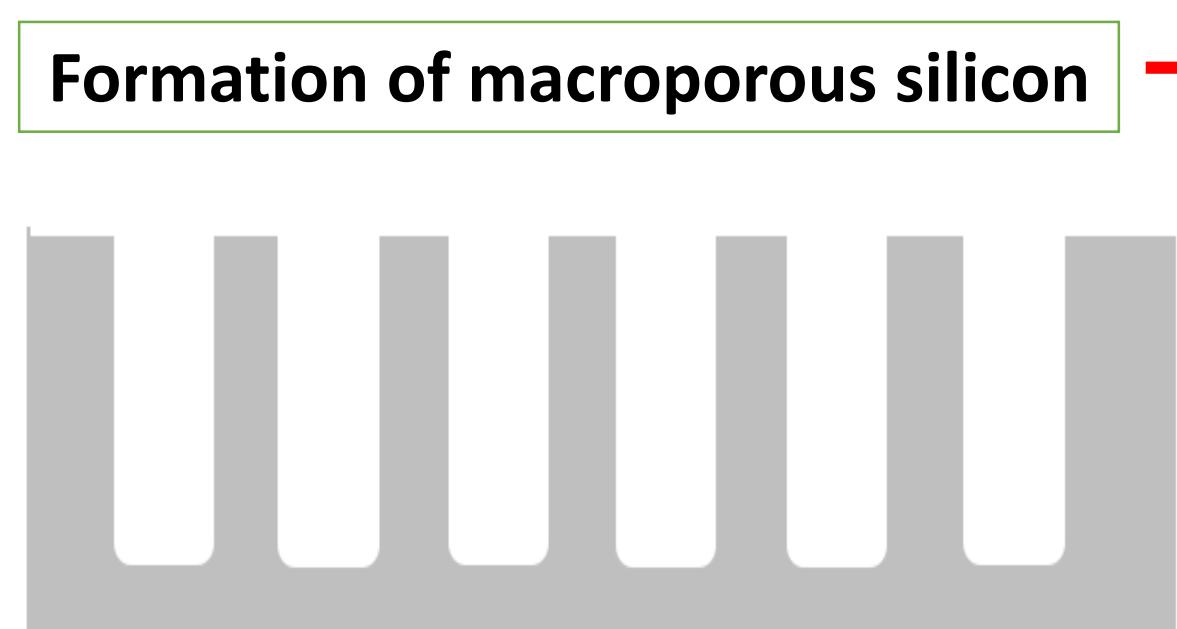


- optical coatings
- a gate insulator in field-effect transistors
- a high-k dielectric in DRAM capacitors

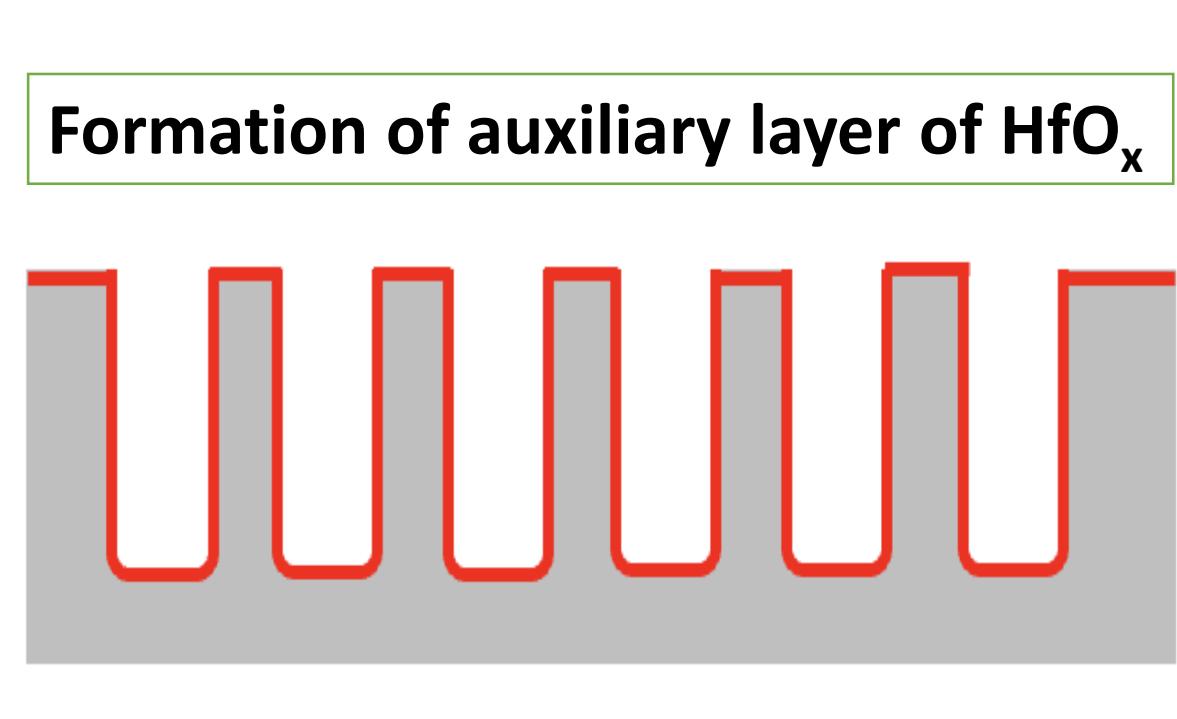
Formation of SERS-substrates



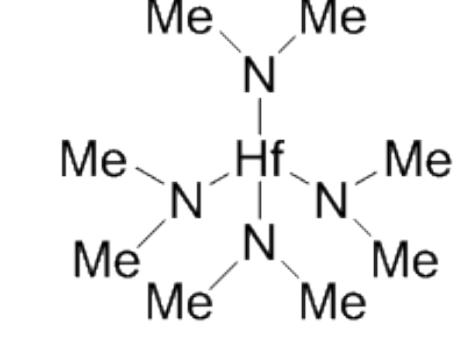
p-type monocrystalline silicon wafer of (100) orientation and 12 Ohm·cm resistivity



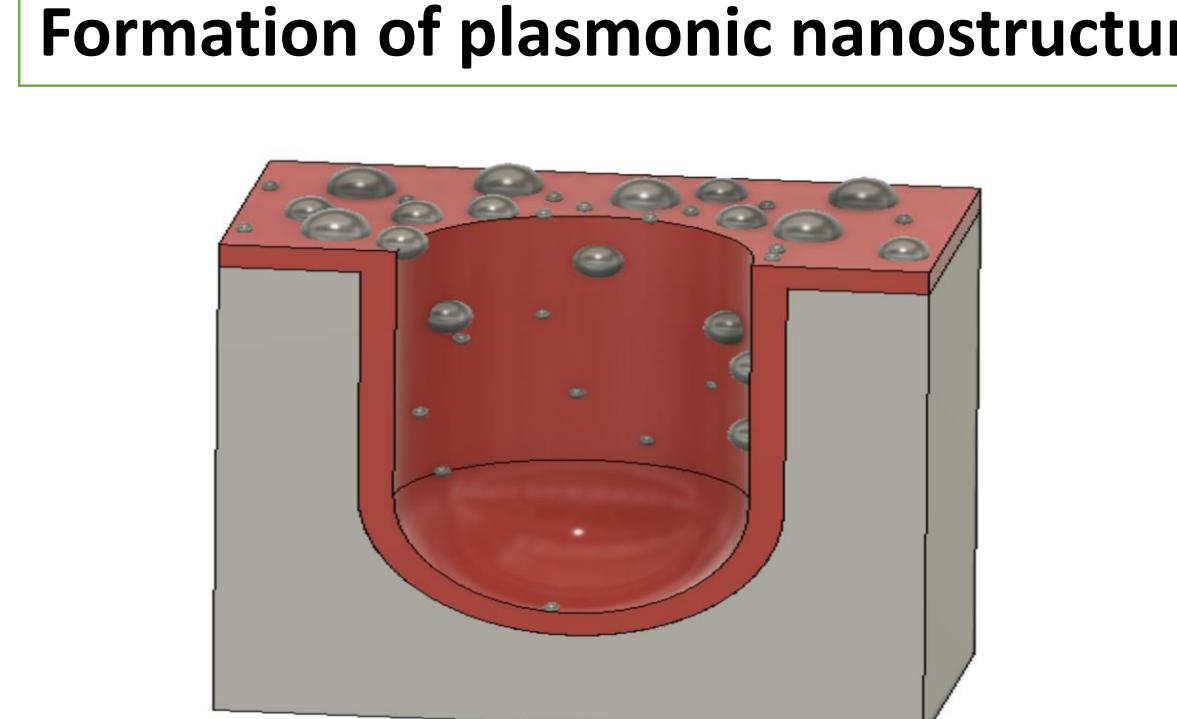
Formation of macroporous silicon → Electrochemical etching of Si wafer in HF-based electrolyte



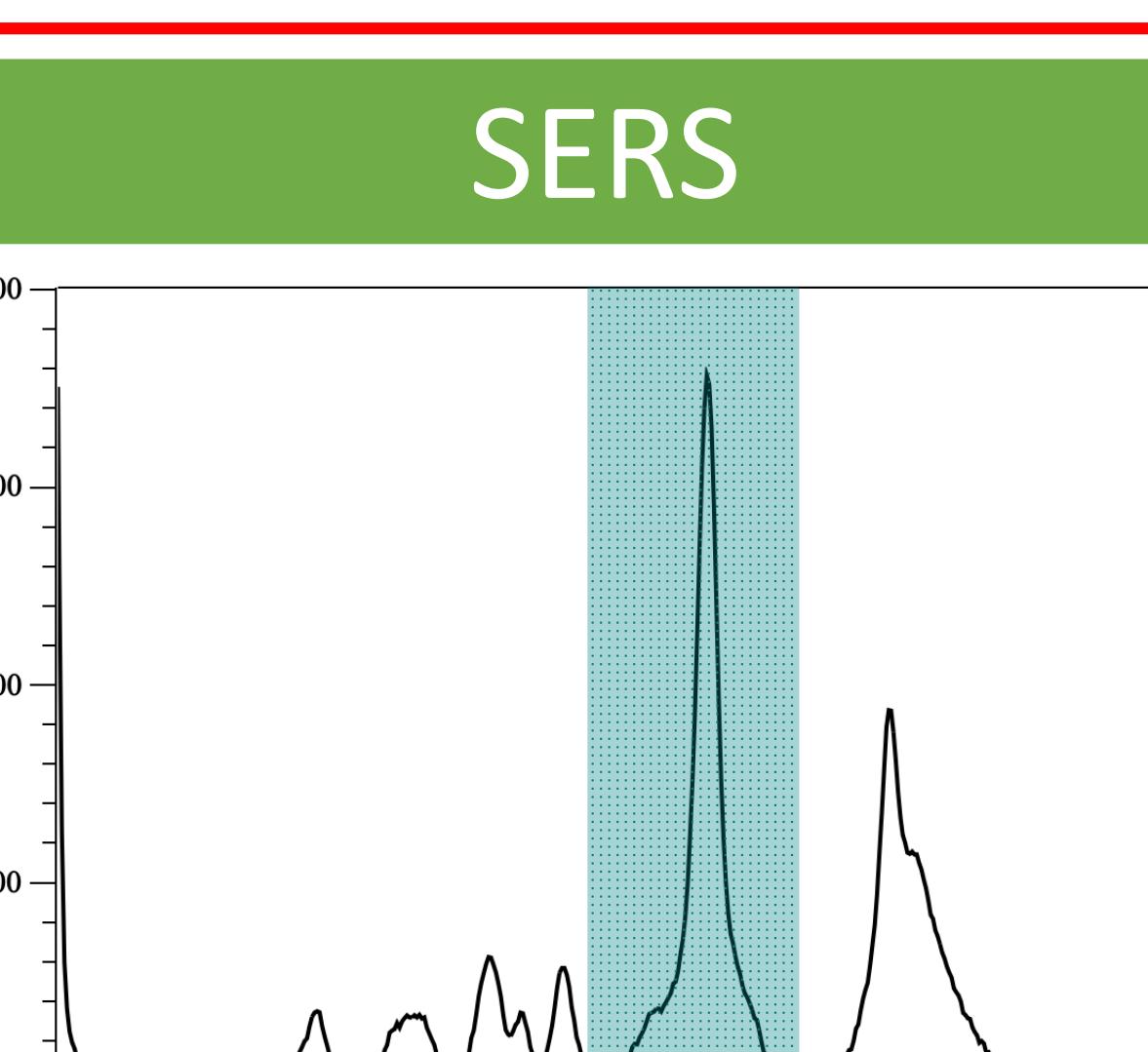
Atomic layer deposition (ALD) of HfO_x
Two precursors: TEMAH Hf[N(CH₂CH₃)(CH₃)₄] and H₂O



Two chemical approaches:
• Immersion deposition of silver
• Silver mirror reaction

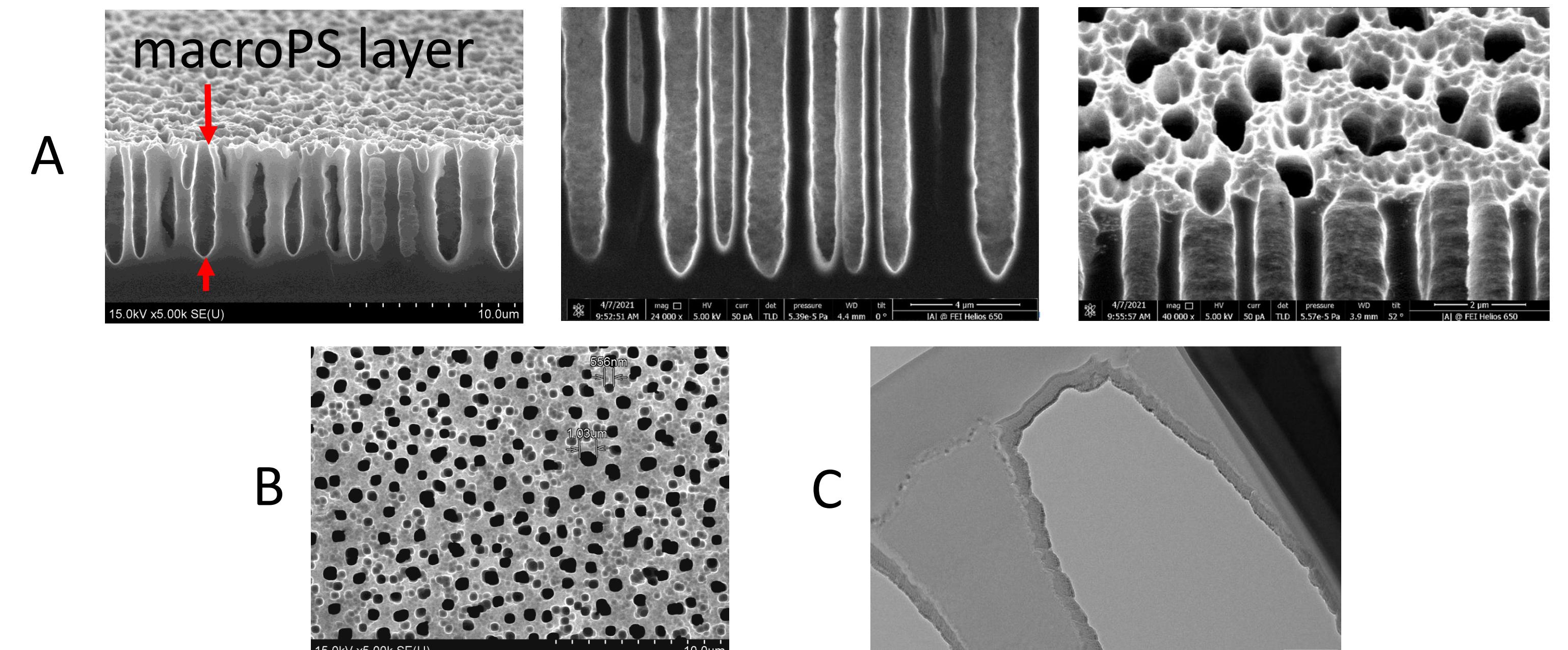


Formation of plasmonic nanostructures

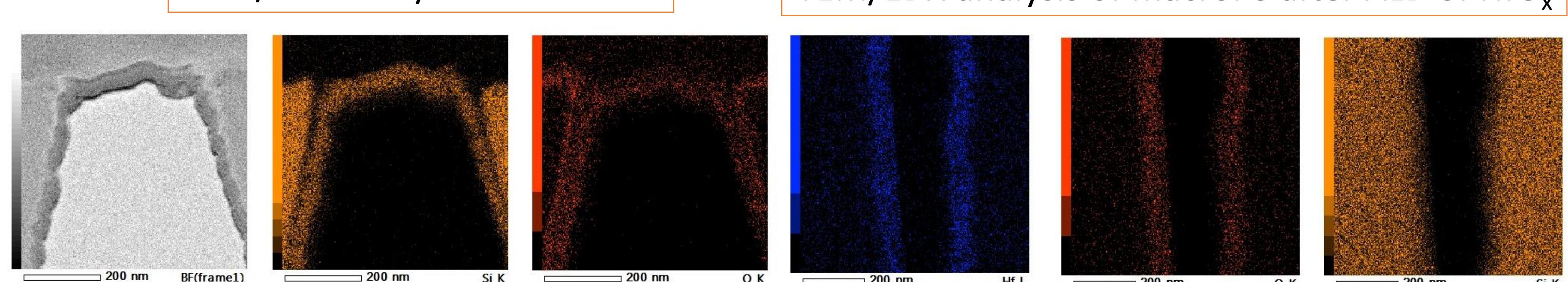


Morphology

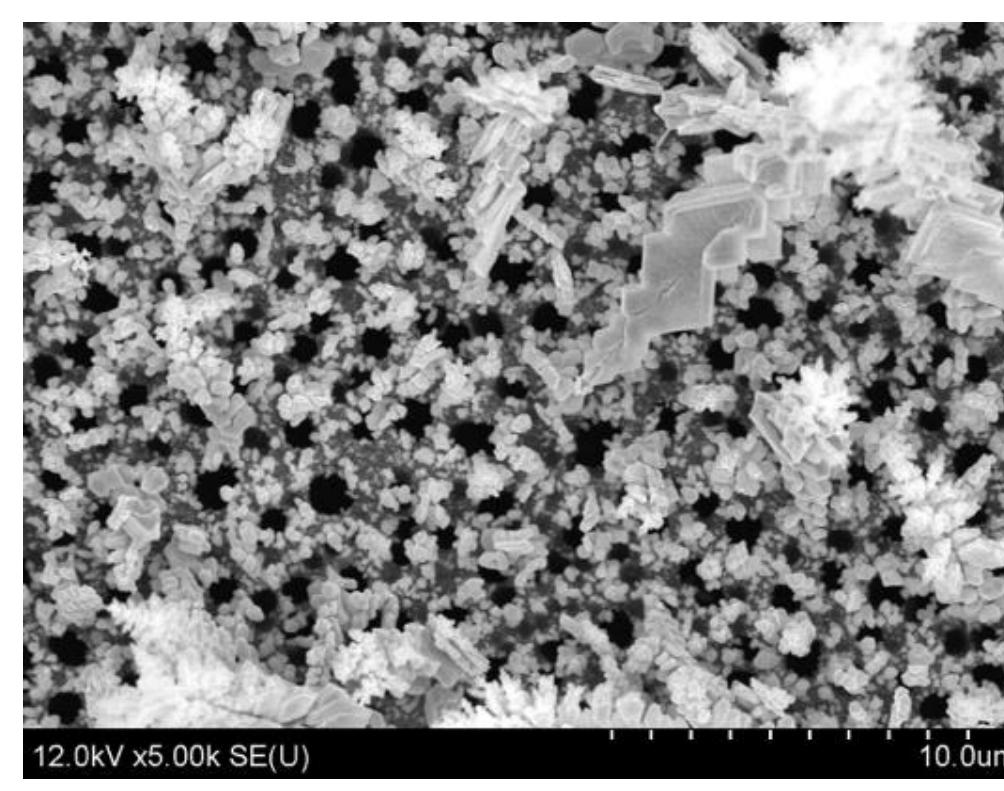
SEM image of macroporous silicon: cross-section (A), top view (B), TEM image (C)



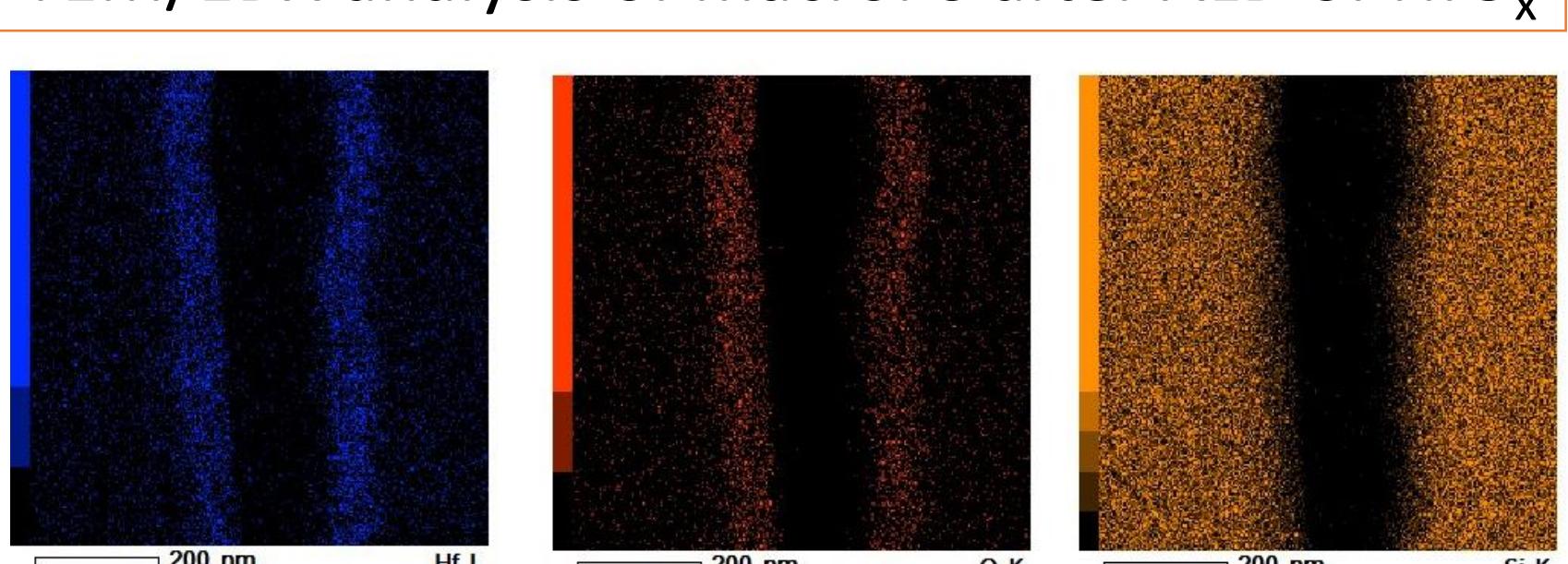
TEM/EDX analysis of macroPS



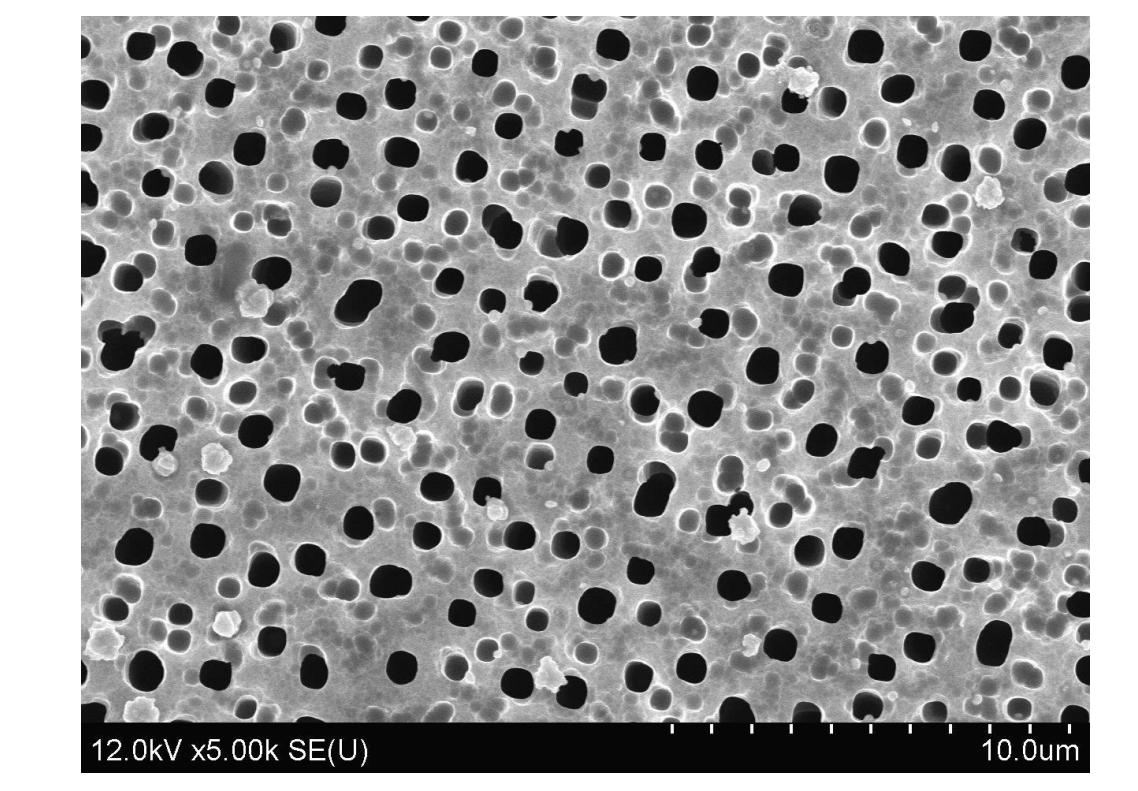
MacroPS/HfO_x after silver mirror reaction



TEM/EDX analysis of macroPS after ALD of HfO_x



MacroPS/HfO_x after immersion deposition of silver



SERS

Laser – 473 nm

Objective – 40x

Excitation time – 1 s

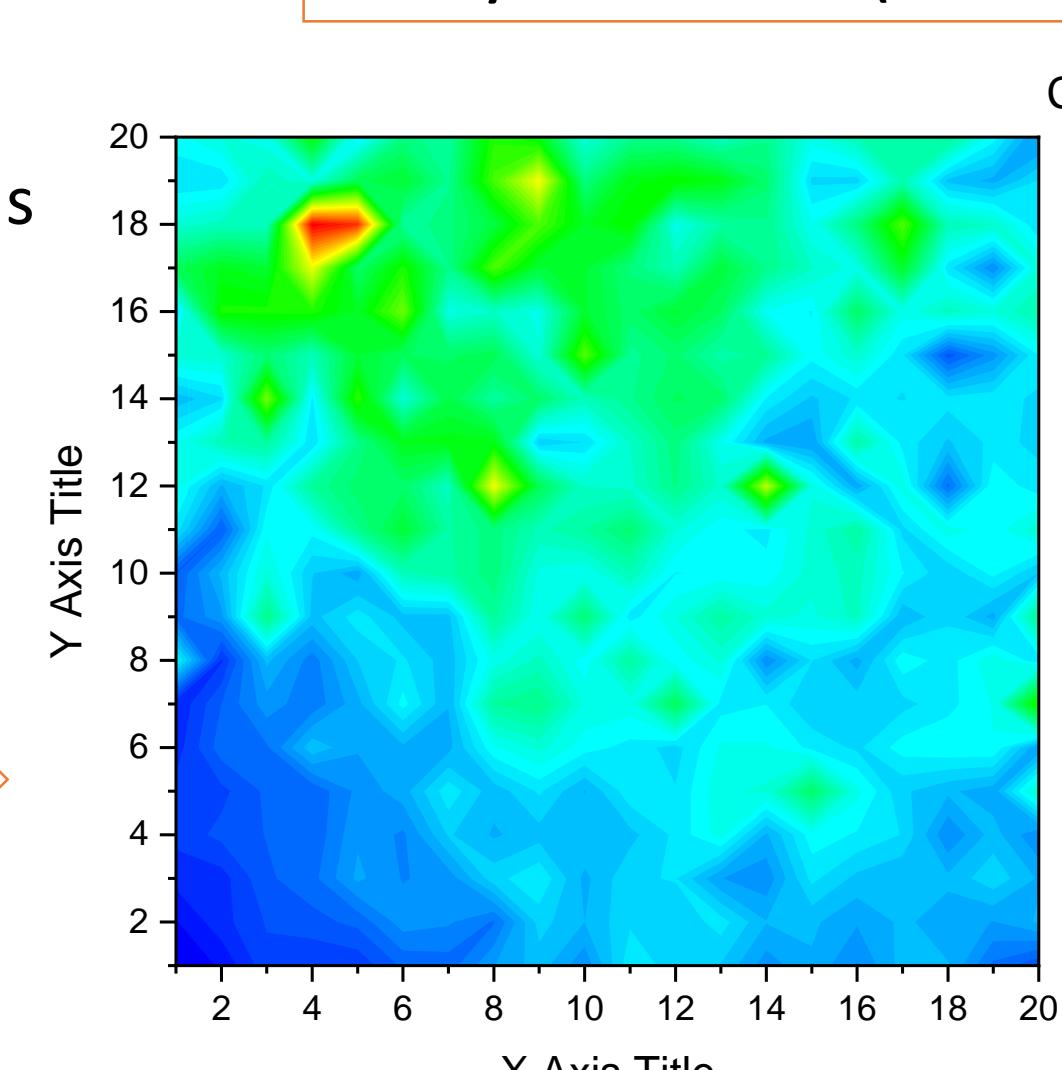
Mapping

340x340 um.

400 spectra

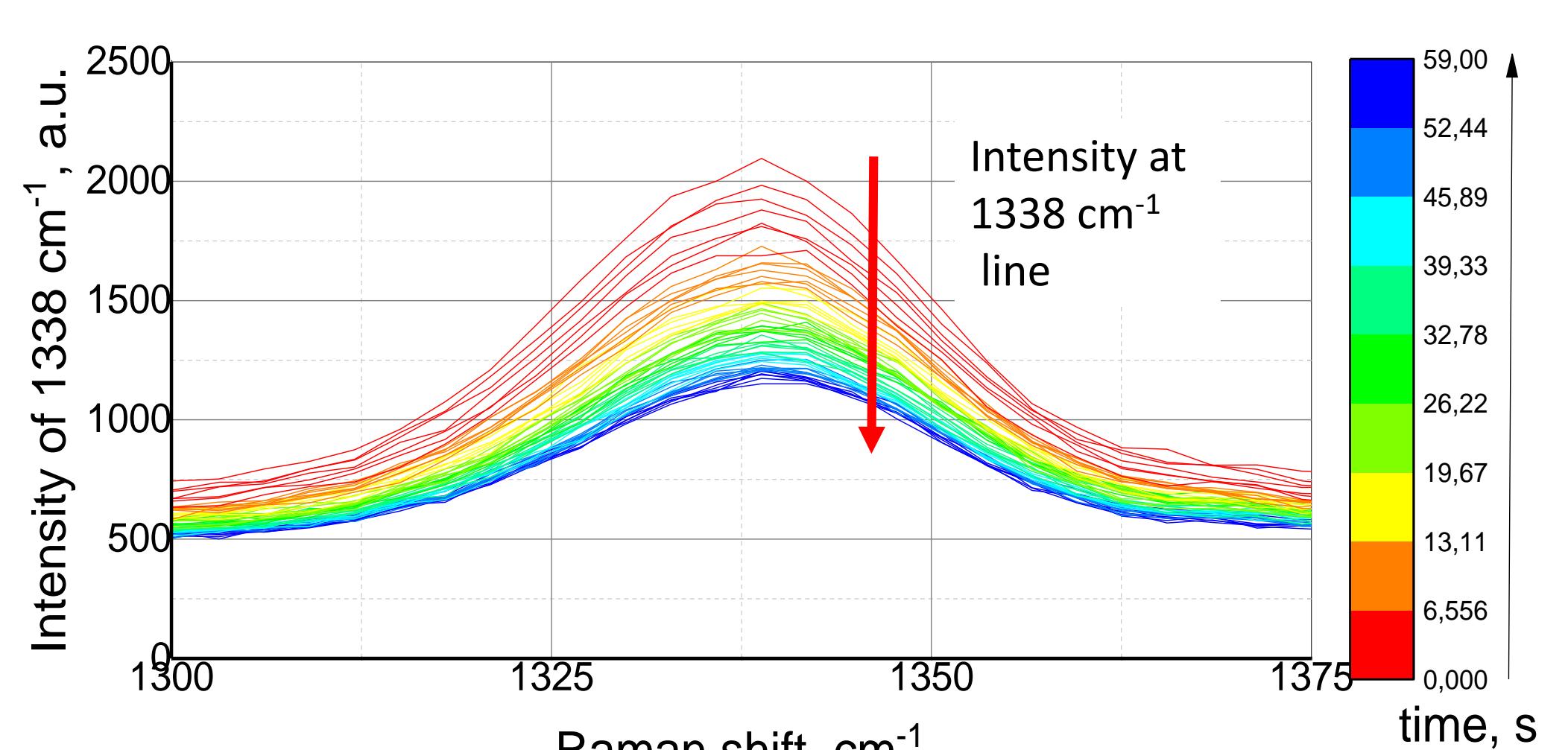
Distribution of intensity at 1338 cm⁻¹ line

Analyte - DTNB (Ellman's Reagent (5,5-dithio-bis-(2-nitrobenzoic acid))) – 10⁻⁵M



Kinetics

Time: 60 s



The research was supported by BRFFR and RFBR (projects №T21PM-136, №20-58-04016).